

Abstract

Provided is an electrostatic chuck device that can repeatedly exhibit initial performance such as a leakage current value, a volume resistivity, and surface roughness while reducing generation of labor and cost as much as possible with considering a refurbishment treatment after use. The electrostatic chuck device includes: a base substrate having a coolant flow path; and an electrostatic chuck having an internal electrode between an insulating layer and a dielectric layer, wherein a side of the dielectric layer serves as a workpiece attraction surface, wherein the dielectric layer of the electrostatic chuck has an alumina coating film composed of Al_2O_3 having a thickness of 1 μm or more and 5 μm or less on a surface thereof, and the workpiece attraction surface has a volume resistivity at room temperature of $1 \times 10^{15} \Omega \cdot \text{cm}$ or more.